

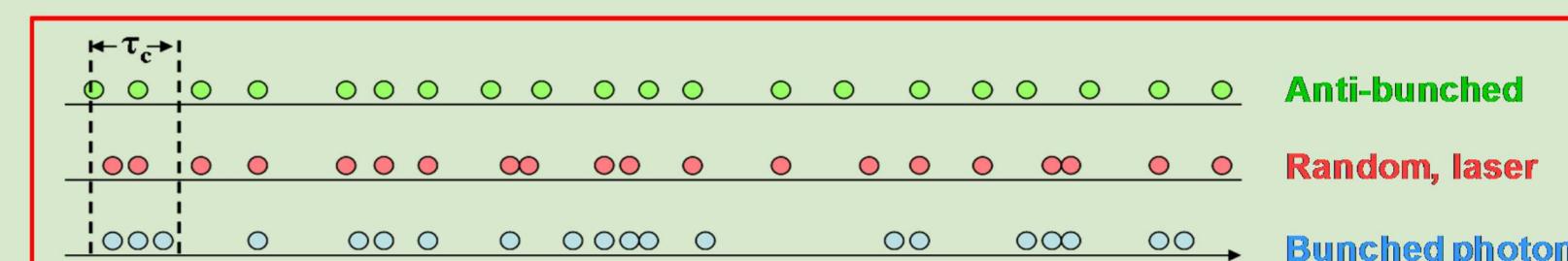
Deterministic Fabrication of Quantum Dots for Quantum Light Sources Using Selective Photoelectrochemical Etching



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What are Quantum Light Sources ?

- ❖ Quantum light sources produce anti-bunched photons
- ❖ For example, single photon sources (SPS): photons are emitted one at a time.



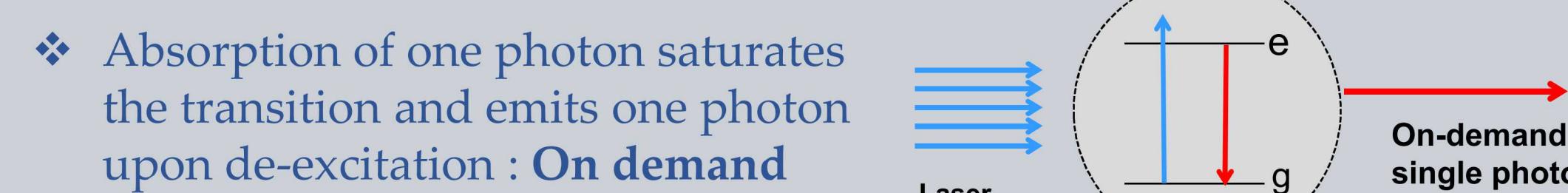
Source: J.S. Lundeen

- ❖ They are important for many applications

- ❖ Quantum key distribution
- ❖ Quantum computing
- ❖ Quantum metrology
- ❖ True random number generation

Why III-nitride quantum dots?

- ❖ Quantum dots (QD) behave like two-level systems and generate one photon at a time



- ❖ III-nitrides based QDs are particularly interesting

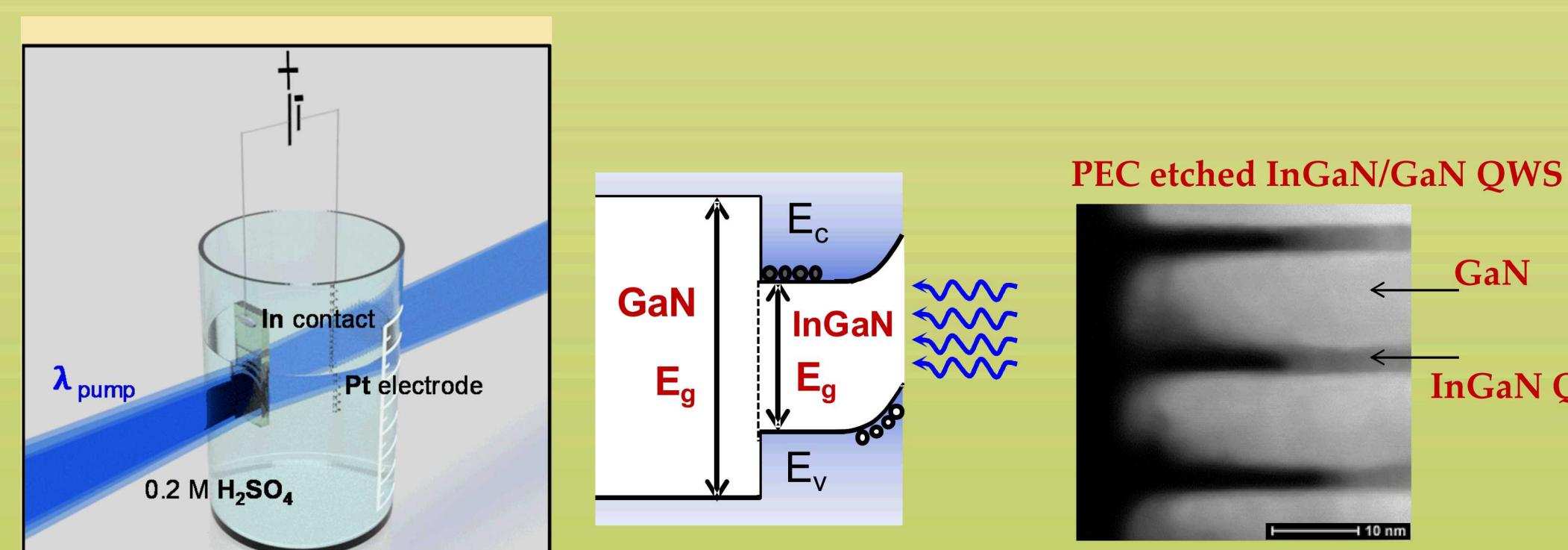
- ❖ Large exciton binding energy (~30 meV) enables room temperature operation
- ❖ Short emitter life-time (~1ns) enables fast repetition rate
- ❖ Path to electrically injected operation and chip-scale integration
- ❖ Can be fabricated with controlled size and deterministic placement → Photo electrochemical etching approach

III-nitride system investigated here: InGaN/GaN

Photoelectrochemical Etching

Electrochemical etching of III-nitride material under illuminated conditions

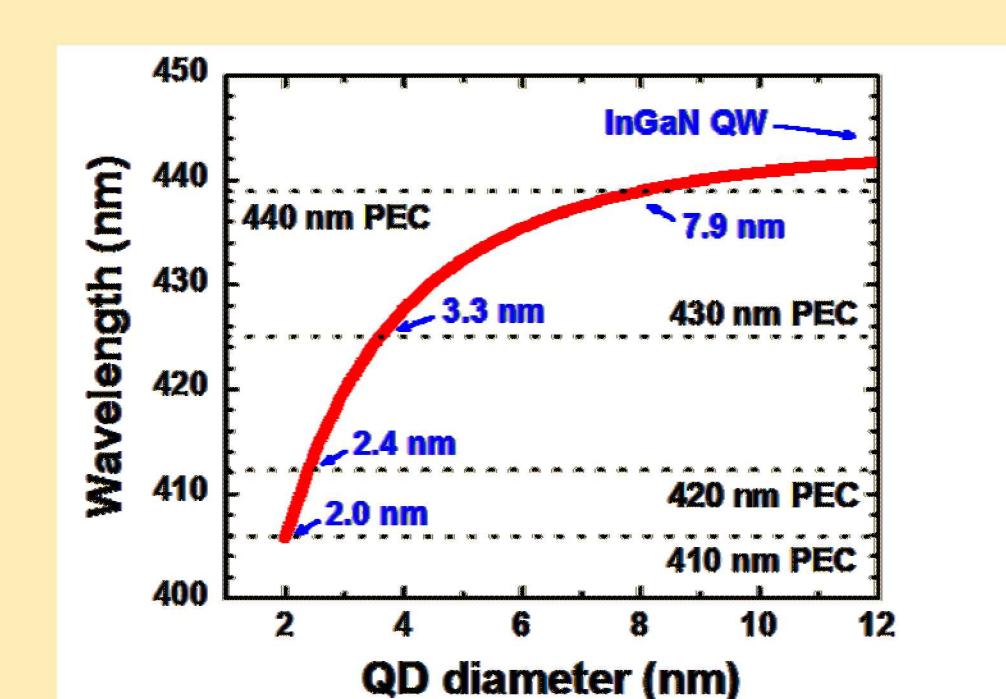
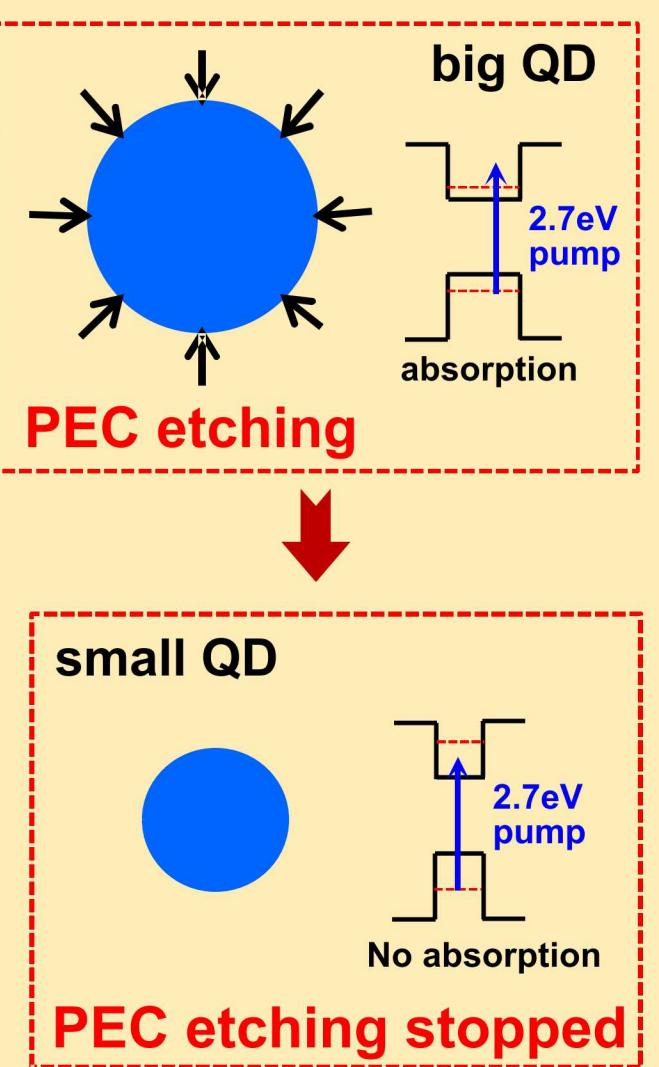
1. The III-nitride material is immersed in a mild acid or base used as electrolyte (e.g. ~0.1 – 0.2 M KOH or H_2SO_4) under light illumination.
2. Etching proceeds at the semiconductor surface due to oxidation by photoexcited holes.
3. Etching is bandgap selective, dopant selective and light intensity depended – provides control



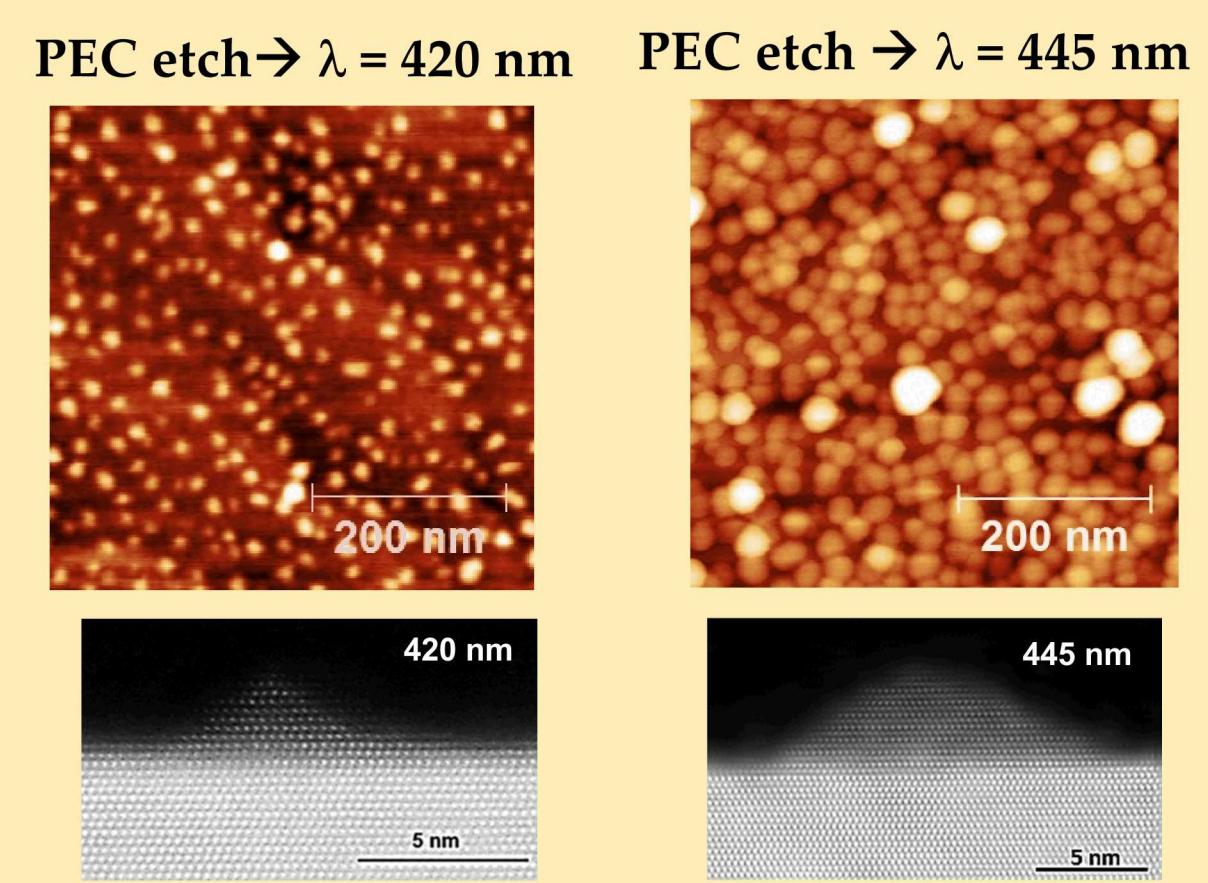
Quantum size control using Photoelectrochemical (PEC) Etching

PEC etch process is self-limiting

- ❖ For QDs, energy gap depends on size
- ❖ As etch proceeds,
 - ❖ QD size gets smaller, band gap goes up
 - ❖ Etch terminated for $E_g > E_{\text{pump}}$
- ❖ QD size depends on the illumination wavelength
- ❖ With narrowband illumination (e.g. laser) monodisperse QDs can be obtained

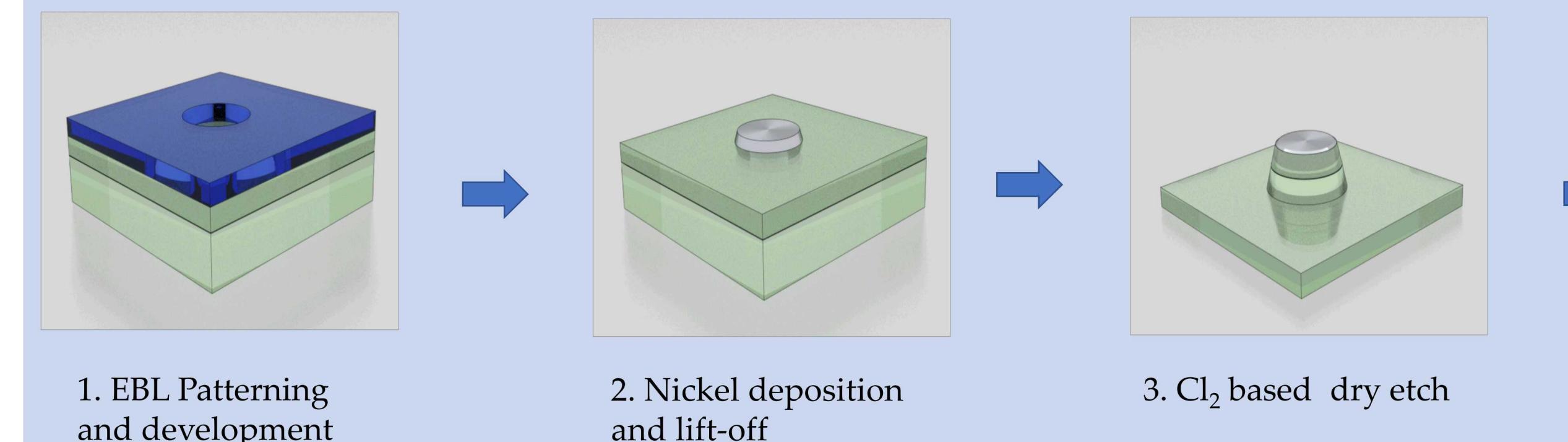


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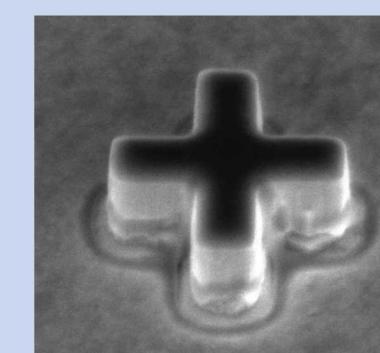


Deterministic placement of PEC etched QDs

To achieve deterministic placement of QDs, an epitaxial stack containing a single quantum well is first patterned using electron beam lithography along with an alignment feature to be used to create subsequent enclosing structure for example a photonic crystal.



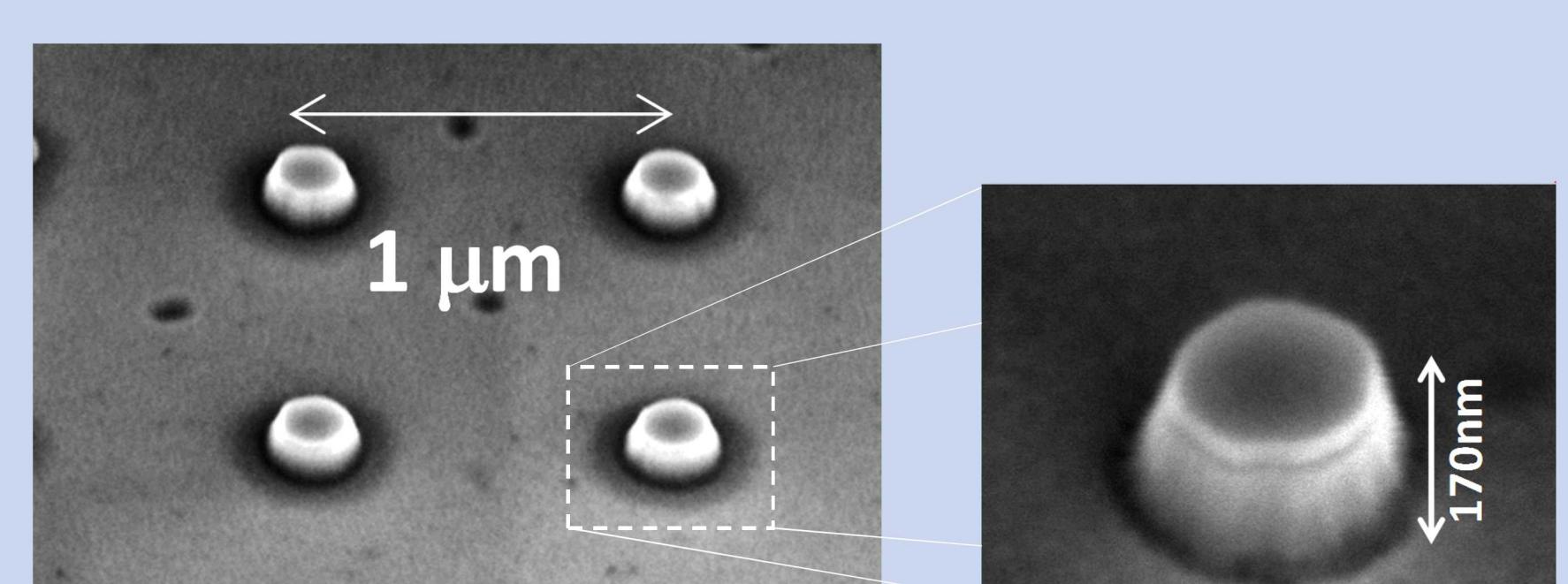
Alignment feature



III-nitride Epitaxial structure



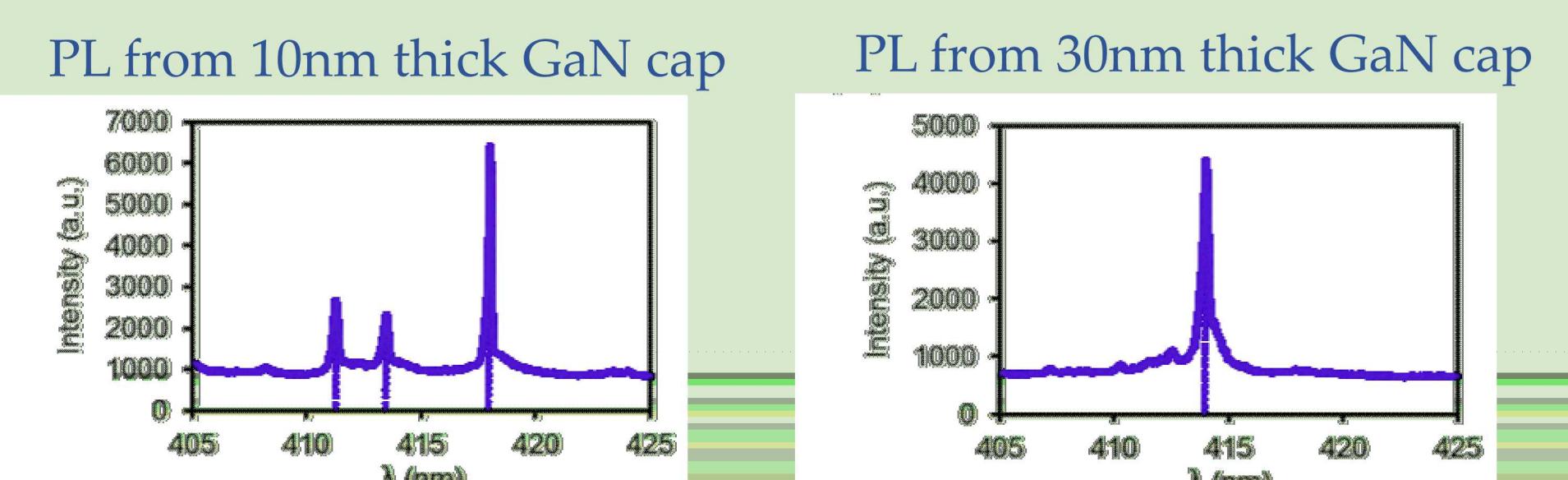
Scanning electron microscope image of QD in nanowire



Optical Measurement

Low temperature photoluminescence collected from PEC etched nanowire

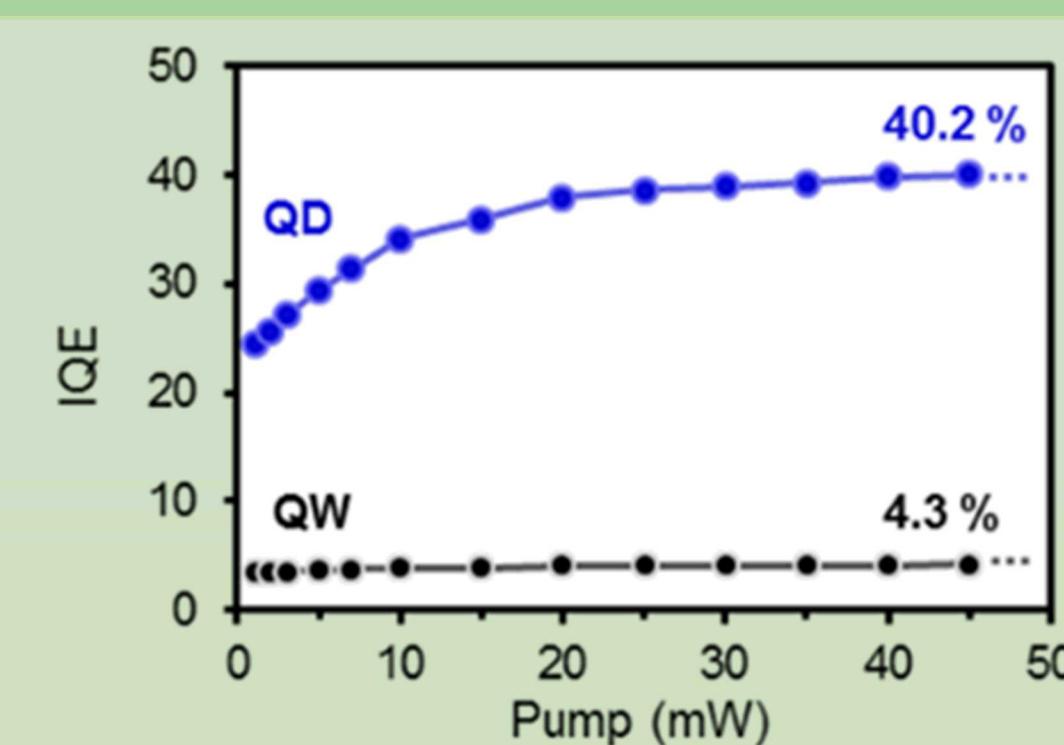
- Multiple or single QD can form depending upon the capping layer thickness



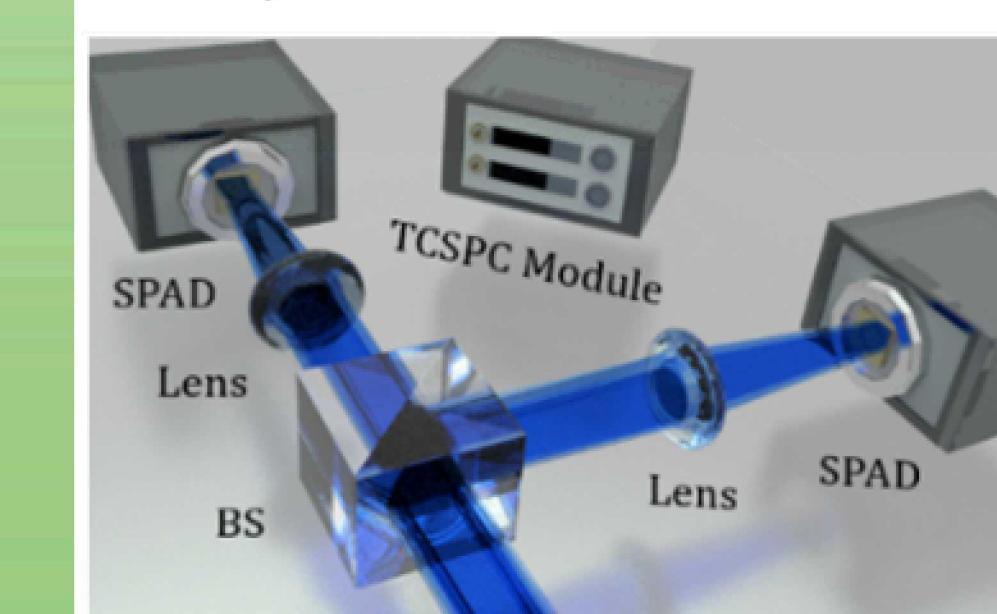
An improvement in internal quantum efficiency is observed for QD vs. the quantum well.

Potential reasons:

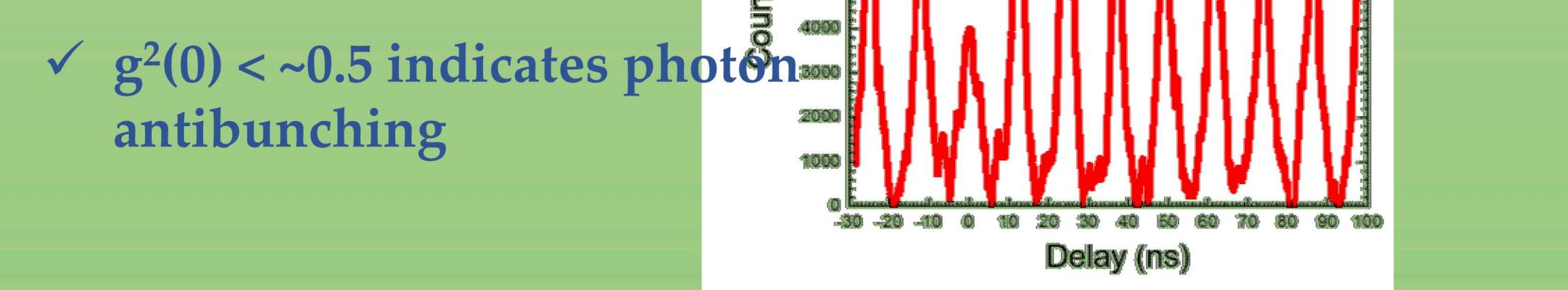
- Strain relaxation and increased carrier confinement in QDs.
- Removal of threading dislocations regions during PEC etching



Hanbury Brown and Twiss (HBT) setup



Second order cross-correlation $g^2(0)$



✓ $g^2(0) < \sim 0.5$ indicates photon antibunching

Summary

- ❖ Quantum light sources are important for quantum information science and technology
- ❖ III-nitride based QDs can enable room temperature, on-demand single photon source.
- ❖ III-nitride QDs can be fabricated at deterministic locations using a combination of aligned patterning and photo electrochemical etch.
- ❖ Photon antibunching can be observed in QD in nanowire structures.

References

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2. X. Xiao, A. J. Fischer, G. T. Wang, P. Lu, D. D. Koleske, M. E. Coltrin, J. B. Wright, S. Liu, I. Brener, G. S. Subramania, and J. Y. Tsao, "Quantum-Size-Controlled Photoelectrochemical Fabrication of Epitaxial InGaN Quantum Dots," *Nano Lett.* 14, 5616-5620 (2014).
3. P. D. Anderson, A. J. Fischer, D. D. Koleske, B. P. Gunning, and G. Subramania, "III-nitride photonic crystal emitters by selective photoelectrochemical etching of heterogeneous quantum well structures," *Optical Materials Express* 8, 3543-3550 (2018).